



REISSUE PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Reissue Application of

Satoshi INOUE et al.

Group Art Unit: 2812

U.S. Patent No.: 6,127,199

Examiner: R. BOOTH

Application No.: 10/748,206

Filed: December 31, 2003

Docket No.: 040852.98

For: MANUFACTURING METHOD OF ACTIVE MATRIX SUBSTRATE, ACTIVE MATRIX SUBSTRATE AND LIQUID CRYSTAL DISPLAY DEVICE

SUPPLEMENTAL DECLARATION FOR REISSUE

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

We, Satoshi INOUE and Tatsuya SHIMODA, hereby declare that:

Every error in the patent which was corrected in the present reissue application, and which is not covered by the prior oath(s) and/or declaration(s) submitted in this application, arose without any deceptive intent on the part of the applicant.

We hereby declare that all statements made herein of my/our own knowledge are true and that all statements made on information and belief are believed to be true; and further these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the U.S. Code and that such willful false statements may jeopardize the validity of the application or any patent reissued thereon.

Date: Feb. 13, 2008

Satoshi INOUE

Date: Feb. 27, 2008

Tatsuya SHIMODA